

*Substitute Specification*

← filed 03/17/2004

**Divisional of Application No. 09/946,486**

**TITLE OF THE INVENTION**

**ALIGNMENT METHOD AND EXPOSURE APPARATUS  
USING THE METHOD**

This application is a divisional application of copending U.S. patent application  
number 09/946,486, filed September 6, 2001.

**FIELD OF THE INVENTION**

The present invention relates to an alignment method and an exposure apparatus using  
the method, and particularly is suitable for an alignment method in semiconductor  
manufacturing and method and apparatuses for manufacturing devices using it.

**BACKGROUND OF THE INVENTION**

Currently, in semiconductor manufacturing, a semiconductor device is fabricated by  
depositing multiple layers successively. In actual semiconductor manufacturing, a method is  
known wherein instead of measuring positions of alignment marks formed in a layer prior to  
exposure, marks are formed in the multiple layers and alignment is performed by measuring  
positions of the marks in multiple layers.